Effect of Source Composition Ratio on YBCO Deposition by a MOCVD Process

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YBCO films were grown on (100) MgO single crystalline substrates by a metal organic chemical vapor deposition (MOCVD) process. Solid type Y(tmhd)₃, Ba(tmhd)₂, and Cu(tmhd)₂ were used as sources. To make single liquid solution, the solid sources were dissolved in tetrahydrofuran (THF). The glass fiber reel-to-reel device was used to supply the sources continuously into the CVD reaction chamber. Heating temperature for the source delivering part was 300. Because the evaporation kinetics of Ba and Cu source is sensitive to a temperature, it was difficult to deposit a 123 film from stoichiometric 123 composition source. The molar ratio of the Ba(tmhd)₂ and Cu(tmhd)₂ was thus varied to find the optimum film composition. The oxygen partial pressure and deposition temperature were also varied to establish the deposition condition. The a-axes oriented film was obtained at low deposition temperature while the c-axis oriented film was obtained at higher temperatures. The a-axis grains were dispersed as a discrete form in the c-axis matrix. Phase formation and film orientation and superconducting transition temperature and film composition are reported.

keywords: MOCVD, c-axis oriented film, composition ratio.

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